



Docket No.: 004066 USA D01/Consilium/Consilium

PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

John F. ARACKAPARAMBIL et al.

Serial No. 10/084,092

Filed: February 28, 2002

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Group Art Unit: 2121

Examiner:

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OCT 10 2003

Technology Center 2100

For: COMPUTER INTEGRATED MANUFACTURING TECHNIQUES

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of the references listed on pages 1 and 2 of Form PTO-1449 are submitted herewith.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott M. Alter". The signature is fluid and cursive, with the first name "Scott" being more prominent.

Scott M. Alter

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SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION
(PTO-1449)ATTY. DOCKET NO.
004066 USA
D01/Consilium/ConsiliumSERIAL NO.
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APPLICANT
John F. ARACKAPARAMBIL et al.

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FILING DATE
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,901,313	05/04/99	Wolf et al.			09/02/97
	6,002,989	12/14/99	Shiba et al.			04/01/97
	6,094,688	07/25/00	Mellen-Garnett et al.			03/12/98
	6,340,602	01/22/02	Johnson et al.			02/12/01
	6,345,288	02/05/02	Reed et al.			05/15/00
	6,368,879	04/09/02	Toprac			09/22/99
	US-2002/0107604	08/08/02	Riley et al.			12/06/00
	6,470,230	10/22/02	Toprac et al.			01/04/00
	6,482,660	11/19/02	Conchieri et al.			03/19/01
	6,567,717	05/20/03	Krivokapic et al.			01/19/00

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 99/59200	11/18/99	WIPO			X	
	WO 01/52319	07/19/01	WIPO			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	Williams, Randy, Dadi Gudmundsson, Kevin Monahan, Raman Nurani, Meryl Stoller and J. George Shanthikumar. October 1999. "Optimized Sample Planning for Wafer Defect Inspection," <i>Semiconductor Manufacturing Conference Proceedings, 1999 IEEE International Symposium on Santa Clara, CA</i> . Piscataway, NJ. pp. 43 - 46.
	23 July 2003. Invitation to Pay Additional Fees and Communication Relating to the Results of the Partial International Search for PCT/US02/19116.
	01 August 2003. Written Opinion for PCT/US01/27406.
	20 August 2003. Written Opinion for PCT/US01/22833.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.